

Alan Howling

List of Publications by Year in descending order

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107
papers

3,168
citations

117625

34
h-index

168389

53
g-index

108
all docs

108
docs citations

108
times ranked

1439
citing authors

#	ARTICLE	IF	CITATIONS
1	Frequency effects in silane plasmas for plasma enhanced chemical vapor deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1992, 10, 1080-1085.	2.1	157
2	Time-resolved measurements of highly polymerized negative ions in radio frequency silane plasma deposition experiments. Journal of Applied Physics, 1994, 75, 1340-1353.	2.5	155
3	Improving plasma uniformity using lens-shaped electrodes in a large area very high frequency reactor. Journal of Applied Physics, 2004, 95, 4559-4564.	2.5	123
4	Diagnostics of particle genesis and growth in RF silane plasmas by ion mass spectrometry and light scattering. Plasma Sources Science and Technology, 1994, 3, 278-285.	3.1	119
5	Negative ion mass spectra and particulate formation in radio frequency silane plasma deposition experiments. Applied Physics Letters, 1993, 62, 1341-1343.	3.3	115
6	Plasma silane concentration as a determining factor for the transition from amorphous to microcrystalline silicon in SiH ₄ /H ₂ discharges. Plasma Sources Science and Technology, 2007, 16, 80-89.	3.1	111
7	Negative hydrogenated silicon ion clusters as particle precursors in RF silane plasma deposition experiments. Journal Physics D: Applied Physics, 1993, 26, 1003-1006.	2.8	106
8	Influences of a high excitation frequency (70 MHz) in the glow discharge technique on the process plasma and the properties of hydrogenated amorphous silicon. Journal of Applied Physics, 1992, 71, 5665-5674.	2.5	100
9	A voltage uniformity study in large-area reactors for RF plasma deposition. Plasma Sources Science and Technology, 1997, 6, 170-178.	3.1	98
10	Particle agglomeration study in rf silane plasmas: In situ study by polarization-sensitive laser light scattering. Journal of Applied Physics, 1996, 80, 2069-2078.	2.5	92
11	Electromagnetic field nonuniformities in large area, high-frequency capacitive plasma reactors, including electrode asymmetry effects. Plasma Sources Science and Technology, 2006, 15, 302-313.	3.1	82
12	Anionic clusters in dusty hydrocarbon and silane plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 535-539.	2.1	75
13	Direct visual observation of powder dynamics in rf plasma-assisted deposition. Applied Physics Letters, 1991, 59, 1409-1411.	3.3	71
14	The physics of plasma-enhanced chemical vapour deposition for large-area coating: industrial application to flat panel displays and solar cells. Plasma Physics and Controlled Fusion, 2000, 42, B353-B363.	2.1	71
15	Sheath impedance effects in very high frequency plasma experiments. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 132-138.	2.1	64
16	Spatiotemporal powder formation and trapping in radio frequency silane plasmas using two-dimensional polarization-sensitive laser scattering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1995, 13, 918-926.	2.1	60
17	Powder dynamics in very high frequency silane plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1992, 10, 1048-1052.	2.1	55
18	Dependence of intrinsic stress in hydrogenated amorphous silicon on excitation frequency in a plasma-enhanced chemical vapor deposition process. Journal of Applied Physics, 1992, 72, 3220-3222.	2.5	53

#	ARTICLE	IF	CITATIONS
19	Mechanisms of Plasma-Seed Treatments as a Potential Seed Processing Technology. <i>Frontiers in Physics</i> , 2021, 9, .	2.1	53
20	Nonuniform radio-frequency plasma potential due to edge asymmetry in large-area radio-frequency reactors. <i>Journal of Applied Physics</i> , 2004, 96, 5429-5440.	2.5	51
21	The role of metastable atoms in argon-diluted silane radiofrequency plasmas. <i>Journal Physics D: Applied Physics</i> , 1994, 27, 1406-1411.	2.8	50
22	R&D around a photoneutralizer-based NBI system (Siphore) in view of a DEMO Tokamak steady state fusion reactor. <i>Nuclear Fusion</i> , 2015, 55, 123020.	3.5	50
23	Silicon oxide particle formation in RF plasmas investigated by infrared absorption spectroscopy and mass spectrometry. <i>Journal Physics D: Applied Physics</i> , 1998, 31, 74-84.	2.8	48
24	Applications of the cavity ring-down technique to a large-area rf-plasma reactor. <i>Plasma Sources Science and Technology</i> , 1999, 8, 448-456.	3.1	47
25	VHF Plasma Deposition: A Comparative Overview. <i>Materials Research Society Symposia Proceedings</i> , 1992, 258, 15.	0.1	45
26	Anion reactions in silane plasma. <i>Journal of Applied Physics</i> , 2002, 91, 5571-5580.	2.5	45
27	High-efficiency p-i-n a-Si:H solar cells with low boron cross-contamination prepared in a large-area single-chamber PECVD reactor. <i>Thin Solid Films</i> , 2004, 451-452, 525-530.	1.8	45
28	Degree of dissociation measured by FTIR absorption spectroscopy applied to VHF silane plasmas. <i>Plasma Sources Science and Technology</i> , 1998, 7, 114-118.	3.1	41
29	From molecules to particles in silane plasmas. <i>Pure and Applied Chemistry</i> , 1996, 68, 1017-1022.	1.9	40
30	Partial-depth modulation study of anions and neutrals in low-pressure silane plasmas. <i>Plasma Sources Science and Technology</i> , 1996, 5, 210-215.	3.1	40
31	Fast equilibration of silane/hydrogen plasmas in large area RF capacitive reactors monitored by optical emission spectroscopy. <i>Plasma Sources Science and Technology</i> , 2007, 16, 679-696.	3.1	40
32	Negative ion source development for a photoneutralization based neutral beam system for future fusion reactors. <i>New Journal of Physics</i> , 2016, 18, 125005.	2.9	39
33	A gas flow uniformity study in large-area showerhead reactors for RF plasma deposition. <i>Plasma Sources Science and Technology</i> , 2000, 9, 205-209.	3.1	35
34	Microcrystalline silicon deposited at high rate on large areas from pure silane with efficient gas utilization. <i>Solar Energy Materials and Solar Cells</i> , 2007, 91, 495-502.	6.2	35
35	Direct current breakdown in gases for complex geometries from high vacuum to atmospheric pressure. <i>Journal Physics D: Applied Physics</i> , 2013, 46, 285205.	2.8	31
36	Visible photoluminescence from hydrogenated silicon particles suspended in a silane plasma. <i>Journal of Applied Physics</i> , 1995, 78, 61-66.	2.5	29

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37	Probe measurements of plasma potential nonuniformity due to edge asymmetry in large-area radio-frequency reactors: The telegraph effect. <i>Journal of Applied Physics</i> , 2005, 97, 123308.	2.5	27
38	Spectroscopic characterization of H ₂ and D ₂ helicon plasmas generated by a resonant antenna for neutral beam applications in fusion. <i>Nuclear Fusion</i> , 2017, 57, 036024.	3.5	27
39	Helicon wave-generated plasmas for negative ion beams for fusion. <i>EPJ Web of Conferences</i> , 2017, 157, 03014.	0.3	27
40	Application of the shaped electrode technique to a large area rectangular capacitively coupled plasma reactor to suppress standing wave nonuniformity. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2006, 24, 1425-1430.	2.1	25
41	Dust Particle Diagnostics in Rf Plasma Deposition of Silicon and Silicon Oxide Films (Invited). <i>Materials Research Society Symposia Proceedings</i> , 1998, 507, 547.	0.1	21
42	Plasma deposition in an ideal showerhead reactor: a two-dimensional analytical solution. <i>Plasma Sources Science and Technology</i> , 2012, 21, 015005.	3.1	21
43	Resonant RF network antennas for large-area and large-volume inductively coupled plasma sources. <i>Plasma Sources Science and Technology</i> , 2013, 22, 055021.	3.1	21
44	Cold Atmospheric Plasma Inactivation of Microbial Spores Compared on Reference Surfaces and Powder Particles. <i>Food and Bioprocess Technology</i> , 2020, 13, 827-837.	4.7	21
45	Optimization of the microcrystalline silicon deposition efficiency. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2007, 25, 1198-1202.	2.1	20
46	Highly Conductive Microcrystalline Silicon Layers for Tunnel Junctions in Stacked Amorphous Silicon based Solar Cells. <i>Materials Research Society Symposia Proceedings</i> , 1991, 219, 469.	0.1	19
47	Fast Deposition of a-Si:H Layers and Solar Cells in a Large-Area (40Å—40 cm ²) VHF-GD Reactor. <i>Materials Research Society Symposia Proceedings</i> , 1999, 557, 121.	0.1	18
48	Reduction of the boron cross-contamination for plasma deposition of p ⁺ n devices in a single-chamber large area radio-frequency reactor. <i>Thin Solid Films</i> , 2004, 468, 222-225.	1.8	17
49	Entering the plasma agriculture field: An attempt to standardize protocols for plasma treatment of seeds. <i>Plasma Processes and Polymers</i> , 2022, 19, e2100152.	3.0	17
50	Central mass and current density measurements in Tokamaks using the discrete Alfvén wave spectrum. <i>Plasma Physics and Controlled Fusion</i> , 1987, 29, 323-339.	2.1	16
51	Reconstruction of the time-averaged sheath potential profile in an argon radiofrequency plasma using the ion energy distribution. <i>Plasma Sources Science and Technology</i> , 1995, 4, 373-378.	3.1	16
52	Non-intrusive plasma diagnostics for the deposition of large area thin film silicon. <i>Thin Solid Films</i> , 2009, 517, 6218-6224.	1.8	16
53	Cavity ring-down spectroscopy to measure negative ion density in a helicon plasma source for fusion neutral beams. <i>Review of Scientific Instruments</i> , 2018, 89, 103504.	1.3	16
54	Latest experimental and theoretical advances in the production of negative ions in caesium-free plasmas. <i>European Physical Journal D</i> , 2021, 75, 1.	1.3	15

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55	Coherent mode activity in the edge of TOSCA Tokamak. <i>Plasma Physics and Controlled Fusion</i> , 1988, 30, 1863-1877.	2.1	14
56	Comment on "Helicon energy uniformity in high-frequency capacitive discharges" [Appl. Phys. Lett. 86, 021501 (2005)]. <i>Applied Physics Letters</i> , 2005, 87, 076101.	3.3	14
57	Negative ion characterization in a helicon plasma source for fusion neutral beams by cavity ring-down spectroscopy and Langmuir probe laser photodetachment. <i>Nuclear Fusion</i> , 2020, 60, 026007.	3.5	14
58	An In Situ FTIR Study of DBD Plasma Parameters for Accelerated Germination of <i>Arabidopsis thaliana</i> Seeds. <i>International Journal of Molecular Sciences</i> , 2021, 22, 11540.	4.1	14
59	First B-dot measurements in the RAID device, an alternative negative ion source for DEMO neutral beams. <i>Fusion Engineering and Design</i> , 2019, 146, 1140-1144.	1.9	13
60	Helicon wave plasma generated by a resonant birdcage antenna: magnetic field measurements and analysis in the RAID linear device. <i>Plasma Sources Science and Technology</i> , 2021, 30, 075023.	3.1	13
61	Electromagnetic sources of nonuniformity in large area capacitive reactors. <i>Thin Solid Films</i> , 2007, 515, 5059-5064.	1.8	12
62	Large Area Deposition of Amorphous and Microcrystalline Silicon by Very High Frequency Plasma. <i>Materials Research Society Symposia Proceedings</i> , 1998, 507, 541.	0.1	11
63	Plasma generation by inductive coupling with a planar resonant RF network antenna. <i>Journal Physics D: Applied Physics</i> , 2012, 45, 082001.	2.8	11
64	Analysis of resonant planar dissipative network antennas for rf inductively coupled plasma sources. <i>Plasma Sources Science and Technology</i> , 2014, 23, 015006.	3.1	11
65	Microstructure, Optoelectronic Properties and Saturated Defect Density of a-Si:H Prepared in VHF-Glow Discharge Using AR and XE Dilution. <i>Materials Research Society Symposia Proceedings</i> , 1992, 258, 135.	0.1	10
66	Global visualization of powder trapping in capacitive RF plasmas by two-dimensional laser scattering. <i>IEEE Transactions on Plasma Science</i> , 1996, 24, 101-102.	1.3	10
67	Ion heating and flows in a high power helicon source. <i>Physics of Plasmas</i> , 2017, 24, 063517.	1.9	10
68	Influence of higher deposition temperature on a-Si:H material properties, powder formation and light-induced degradation, using the VHF (70 MHz) glow discharge technique. <i>Journal of Non-Crystalline Solids</i> , 1993, 164-166, 59-62.	3.1	9
69	Measurements and consequences of nonuniform radio frequency plasma potential due to surface asymmetry in large area radio frequency capacitive reactors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2005, 23, 922-926.	2.1	9
70	Resonant planar antenna as an inductive plasma source. <i>Journal of Applied Physics</i> , 2012, 111, 083305.	2.5	9
71	Advantages and Limitations of Surface Analysis Techniques on Plasma-Treated <i>Arabidopsis thaliana</i> Seeds. <i>Frontiers in Materials</i> , 2021, 8, .	2.4	9
72	Plasma diagnostics as a tool for process optimization: the case of microcrystalline silicon deposition. <i>Plasma Physics and Controlled Fusion</i> , 2007, 49, B411-B418.	2.1	8

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73	Uniformity of silicon microcrystallinity in large area RF capacitive reactors. Progress in Photovoltaics: Research and Applications, 2008, 16, 687-691.	8.1	8
74	Application of Thomson scattering to helicon plasma sources. Journal of Plasma Physics, 2020, 86, .	2.1	8
75	Experimental study of wakefields driven by a self-modulating proton bunch in plasma. Physical Review Accelerators and Beams, 2020, 23, .	1.6	8
76	Generation of Whistler-Wave Heated Discharges with Planar Resonant rf Networks. Physical Review Letters, 2013, 111, 125005.	7.8	7
77	Complex image method for RF antenna-plasma inductive coupling calculation in planar geometry. Part I: basic concepts. Plasma Sources Science and Technology, 2015, 24, 065014.	3.1	7
78	Input silane concentration effect on the a-Si:H to μ c-Si:H transition width. Solar Energy Materials and Solar Cells, 2010, 94, 432-435.	6.2	6
79	Hydrogen-dominated plasma, due to silane depletion, for microcrystalline silicon deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2010, 28, 989-995.	2.1	6
80	Low ion energy RF reactor using an array of plasmas through a grounded grid. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, .	2.1	6
81	Industrial plasmas in academia. Plasma Physics and Controlled Fusion, 2015, 57, 014010.	2.1	6
82	RNA Sequencing of Arabidopsis thaliana Seedlings after Non-Thermal Plasma-Seed Treatment Reveals Upregulation in Plant Stress and Defense Pathways. International Journal of Molecular Sciences, 2022, 23, 3070.	4.1	6
83	Radio frequency breakdown between structured parallel plate electrodes with a millimetric gap in low pressure gases. Physics of Plasmas, 2010, 17, 102111.	1.9	5
84	Funnelling of rf current via a plasmoid through a grid hole in an rf capacitive plasma reactor. Plasma Sources Science and Technology, 2013, 22, 055006.	3.1	5
85	Complex image method for RF antenna-plasma inductive coupling calculation in planar geometry. Part II: measurements on a resonant network. Plasma Sources Science and Technology, 2015, 24, 065015.	3.1	5
86	Proton Bunch Self-Modulation in Plasma with Density Gradient. Physical Review Letters, 2020, 125, 264801.	7.8	5
87	Development of a plasma electroacoustic actuator for active noise control applications. Journal Physics D: Applied Physics, 2020, 53, 495202.	2.8	5
88	Plasma generation by inductive coupling with a planar resonant RF network antenna. Journal Physics D: Applied Physics, 2012, 45, 409502.	2.8	4
89	Electromagnetic, complex image model of a large area RF resonant antenna as inductive plasma source. Plasma Sources Science and Technology, 2017, 26, 035010.	3.1	4
90	Two-fluid solutions for Langmuir probes in collisionless and isothermal plasma, over all space and bias potential. Physics of Plasmas, 2018, 25, 093519.	1.9	4

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91	Two-fluid plasma model for radial Langmuir probes as a converging nozzle with sonic choked flow, and sonic passage to supersonic flow. <i>Physics of Plasmas</i> , 2019, 26, 044502.	1.9	4
92	Negative hydrogen ion dynamics inside the plasma volume of a linear device: Estimates from particle-in-cell calculations. <i>Physics of Plasmas</i> , 2021, 28, 063503.	1.9	4
93	On the powder formation in industrial reactive RF plasmas. , 2000, , 169-176.		4
94	Rapid deposition of hydrogenated microcrystalline silicon by a high current DC discharge. <i>Thin Solid Films</i> , 2001, 383, 11-14.	1.8	3
95	Slip Ring Test Assembly With Increased Breakdown Voltage Limit for High-Voltage Bus Satellites. <i>IEEE Aerospace and Electronic Systems Magazine</i> , 2020, 35, 32-36.	1.3	3
96	Experimental study of extended timescale dynamics of a plasma wakefield driven by a self-modulated proton bunch. <i>Physical Review Accelerators and Beams</i> , 2021, 24, .	1.6	3
97	Gas Phase and Particle Diagnostic of Hmdso Plasmas by Infrared Absorption Spectroscopy. <i>Materials Research Society Symposia Proceedings</i> , 1998, 544, 65.	0.1	2
98	Gas breakdown mitigation in satellite slip rings. <i>Aerospace Science and Technology</i> , 2019, 85, 229-233.	4.8	2
99	A 1.5D fluid Monte Carlo model of a hydrogen helicon plasma. <i>Plasma Physics and Controlled Fusion</i> , 2022, 64, 055012.	2.1	2
100	The effect of Lower Hybrid Current Drive on the discrete Alfven wave spectrum. <i>Plasma Physics and Controlled Fusion</i> , 1987, 29, 1631-1636.	2.1	1
101	RF bias to suppress post-oxidation of Si:H films deposited by inductively-coupled plasma using a planar RF resonant antenna. <i>Vacuum</i> , 2018, 147, 58-64.	3.5	1
102	Magnetic field configurational study on a helicon-based plasma source for future neutral beam systems. <i>Plasma Sources Science and Technology</i> , 2019, 28, 095005.	3.1	1
103	Radio frequency inductively coupled discharges in thermal plasmas. , 0, , .		1
104	Power laws for the spatial dependence of electrical parameters in the high-voltage capacitive RF sheath. <i>IEEE Transactions on Plasma Science</i> , 2000, 28, 1713-1719.	1.3	0
105	Study of the microstructure transition width from amorphous to microcrystalline silicon as a function of the input silane concentration. , 2009, , .		0
106	RF breakdown in low pressure gases in small (millimetric) gaps with non-planar surfaces. , 2010, , .		0
107	Multiple dehydrogenation reactions of negative ions in low pressure silane plasma chemistry. <i>Plasma Sources Science and Technology</i> , 2020, 29, 105015.	3.1	0